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What is claimed is:

1. A dielectric coating for use on a conductive substrate comprising:

a silicone composition of the formula:

[RSiO<sub>(4-x)/2</sub>]<sub>n</sub> wherein x=1-4 and wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy groups or a combination of the above or monovalent radicals independently selected from alkyl, aryl, alylamide, arylamide, alkylamino groups and arylamino radicals (when 1 < x < 4);

said dielectric coating having a network structure.

2. The dielectric coating of Claim 1 wherein the silicone composition comprises a silsesquioxane compound of the formula:

[RSiO<sub>3/2</sub>]<sub>n</sub> wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy or a combination of the above or monovalent radicals independently selected from alkyl, aryl, alylamide, arylamide, alkylamino groups and arylamino radicals (when 1<x<4) (when 1<x<4).

3. The dielectric coating of Claim 2 wherein the silsesquioxane compound further includes silanol units of the formula:  $[Rsi (OH)_xO_y \text{ where } x+y=3 \text{ and } \text{ which can be siliylated with appropriate organisiloxanes to produce corresponding silylated polysilsesquioxanes.}$ 

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4. The dielectric coating of Claim 1 wherein the silicone composition comprises a polymethyl silsesquioxane of the formula:

[CH 3SiO (3/2)]n.

5. The dielectric coating of Claim 1 wherein the silicone composition

comprises a silsesquioxane copolymer of the formula:

 $R^1{}_aR^2{}_bR^3{}_cSiO_{(4-a-b-c)/2}$ , wherein: a is zero or a positive number, b is zero or a positive number, c is zero or a positive number, with the provisos that  $0.8 \le (a+b+c) \le 3.0$  and wherein the copolymer has an average of at least  $2\ R^1$  groups per molecule, and each  $R^1$  is a functional group independently selected from the group consisting of hydrogen atoms and monovalent hydrocarbon groups having aliphatic unsaturation, and each  $R^2$  and each  $R^3$  are monovalent hydrocarbon groups independently selected from the group consisting of nonfunctional groups and  $R^1$ .

- 6. The dielectric coating of Claim 5 wherein R<sup>1</sup> is an alkenyl group and R<sup>2</sup> and R<sup>3</sup> are nonfunctional groups selected from the group consisting of alkyl and aryl groups.
- 7. The dielectric coating of Claim 6 wherein R<sup>1</sup> is selected from the group consisting of vinyl and allyl groups.
- 8. The dielectric coating of Claim 6 wherein R<sup>2</sup> and R<sup>3</sup> are selected from the group consisting of methyl, ethyl, isopropyl, n-butyl, and isobutyl groups.
- 9. The dielectric coating of Claim 1 wherein the silicone composition comprises a phenyl-methyl siloxane compound of the formula:

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[(MeSiO<sub>3</sub>/<sub>2</sub>)<sub>0.25</sub>(PhSiO<sub>3</sub>/<sub>2</sub>)<sub>0.15</sub>(Ph<sub>2</sub>SiO)<sub>0.50</sub>

10. A substrate structure comprising:

a conductive material;

a dielectric coating disposed on a surface of the conductive material

said dielectric coating comprising a slicone composition of the formula:

 $[RSiO_{(4-x)/2}]_n$  wherein x=1-4 and wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy groups or a combination of the above or monovalent radicals independently selected from alkyl, aryl, alylamide, arylamide, alkylamino groups and arylamino radicals (when 1<x<4);

said dielectric coating having a network structure.

11. The substrate of Claim 10 wherein the silicone composition comprises a silsesquioxane compound of the formula:

[RSiO<sub>3/2</sub>]<sub>n</sub> wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy or a combination of the above or monovalent radicals independently selected from alkyl, aryl, alylamide, arylamide, alkylamino groups and arylamino radicals (when 1 < x < 4) (when 1 < x < 4).

12. The substrate of Claim 11 wherein the silsesquioxane compound further includes silanol units of the formula: [Rsi (OH)<sub>x</sub>O<sub>y</sub> where x+y=3 and which can be siliplated with appropriate organisiloxanes to produce corresponding silylated polysilsesquioxanes.

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13. The substrate of Claim 10 wherein the silicone composition comprises a polymethyl silsesquioxane of the formula:

 $[CH_3SiO_{(3/2)}]_n$ .

14. The substrate of Claim 10 wherein the silicone composition

comprises a silsesquioxane copolymer of the formula:

 $R^1{}_aR^2{}_bR^3{}_cSiO_{(4-a-b-c)/2}$ , wherein: a is zero or a positive number, b is zero or a positive number, c is zero or a positive number, with the provisos that  $0.8 \le (a+b+c) \le 3.0$  and wherein the copolymer has an average of at least  $2~R^1$  groups per molecule, and each  $R^1$  is a functional group independently selected from the group consisting of hydrogen atoms and monovalent hydrocarbon groups having aliphatic unsaturation, and each  $R^2$  and each  $R^3$  are monovalent hydrocarbon groups independently selected from the group consisting of nonfunctional groups and  $R^1$ .

- 15. The substrate of Claim 14 wherein  $R^1$  is an alkenyl group and  $R^2$  and  $R^3$  are nonfunctional groups selected from the group consisting of alkyl and aryl groups.
- 16. The substrate of Claim 15 wherein R<sup>1</sup> is selected from the group consisting of vinyl and allyl groups.
- 17. The substrate of Claim 15 wherein R<sup>2</sup> and R<sup>3</sup> are selected from the group consisting of methyl, ethyl, isopropyl, n-butyl, and isobutyl groups.

18. The substrate of Claim 1 wherein the silicone composition comprises a phenylmethyl siloxane compound of the formula:

[(MeSiO3/2)0.25(PhSiO3/2)0.15(Ph2SiO)0.50.